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(71) Applicant: MERCK PATENT GMBH [DE/DE]; Frankfurter Straße 250, 64293 Darmstadt (DE).

(72) Inventors: CHEN, Hung-Yang; c/o EMD Performance Materials Corp., 70 Meister Avenue, Branchburg, New Jersey 08876 (US). CHEN, Chunwei; c/o EMD Performance Materials Corp., 70 Meister Avenue, Branchburg, New Jersey 08876 (US). CARJA, Ionela Daniela; c/o EMD Performance Materials Corp., 70 Meister Avenue, Branchburg, New Jersey 08876 (US). DAMMEL, Ralph R.; c/o EMD Performance Materials Corp., 70 Meister Avenue, Branchburg, New Jersey 08876 (US).

(74) Agent: RIPPEL, Hans Christoph; Patentanwälte Isenbruck Bösl Hörschler PartG mbB, Seckenheimer Landstraße 4, 68163 Mannheim (DE).

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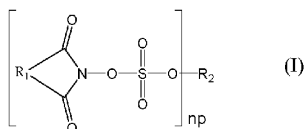
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(54) Title: PHOTOACTIVE COMPOUNDS



(57) Abstract: A covalent compound free of any fluoroalkyls, any perfluoroalkyls or mixtures of fluoroalkyls and perfluoroalkyls comprising an imide N-(carbonylcarbami-do) aryl sulfate moiety. In one of this compound it has structure (I), wherein R<sub>1</sub> is a linking group selected from the group consisting of an unsubstituted alkylene, a substituted alkylene, an unsubstituted vinylen, a substituted vinylen, an unsubstituted arylene, and a substituted arylene, where these linking groups are free of any fluoroalkyls, any perfluoroalkyls or mixtures of fluoroalkyls and perfluoroalkyls, and R<sub>2</sub> is an unsubstituted aryl or a substituted aryl which are free of any fluoroalkyls, any perfluoroalkyls or mixtures of fluoroalkyls and perfluoroalkyls and np is 1, 2, 3, 4 or 5. A positive or negative chemically amplified photoresist composition comprising as a PAG component said covalent compound. A process of forming a positive or negative photoresist patter respectively using said positive or negative chemically amplified photoresists.

WO 2024/223739 A1